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DEC 0 7 2004
PATENT & TRADEMARK

Docket No.: Z&P-INFP10443

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date indicated below.

By: ______________________ Date: December 3, 2004

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patentee : Ernst-Christian Richter et al.
Patent No. : 6,746,827
Issued : June 8, 2004
Title : Process for Structuring a Photoresist Layer

Docket No. : Z&P-INFP10443
Customer No. : 24131

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. 1.501

Hon. Commissioner for Patents

Sir:

In accordance with 37 C.F.R. 1.501 copies of the following patents and/or publications are submitted herewith:

United States Patent No. 5,234,793 (Sebald et al.), dated August 10, 1993.

This document relates to a photolithographic method for a dimensionally accurate photolithographic transfer of sub-µm structures in a bilayer technique. the method includes the steps of applying a photolithographically structurable second resist layer, which includes anhydride groups as reactive groups, onto a first planarizing resist layer, exposing and developing the second resist layer in desired regions for generating a structure, and subjecting the resultant structure so produced to a chemical treatment with a bulging agent, which causes a bulging of the resist structures by reacting with the reactive groups in the second layer (see, for instance, claim 1). By this method, the critical dimension which is achievable with the photolithographic method may be further reduced.

method steps of independent claim 1 of the instant U.S. patent. We are, therefore, of the opinion that the newly introduced prior art document is only relevant regarding dependent claim 25, which states that the film-forming polymer includes one of anhydride structures and succinic anhydride structures.

For the above-outlined reasons, it is believed that the enclosed prior art is less pertinent than the prior art previously submitted or cited by the Examiner. Kindly place the references in the Patent Office file wrapper.

Respectfully submitted,

For Patentees

LAURENCE A. GREENBERG
REG. NO. 29,308

Date: December 3, 2004

Lerner And Greenberg, P.A.
Post Office Box 2480
Hollywood, FL 33022-2480
Tel: (954) 925-1100
Fax: (954) 925-1101

/bmb

Sheet 1 of 1

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U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(37 CFR 1.98(b))

Attorney Docket No.: Z&P-INFP10443
Patent No. 6,746,827

Patentee
Ernst-Christian Richter et al.

Issued
June 8, 2004

U.S. PATENT DOCUMENTS

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	5,234,793	08/10/93	Sebald et al.			
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						

FOREIGN PATENT DOCUMENT

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES	NO
	J							
	K							
	L							
	M							
	N							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	O	
	P	

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.